

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Toshikazu TACHIKAWA et al.

Serial No. [NEW]

Filed January 24, 2002

NEGATIVE-WORKING PHOTORESIST  
COMPOSITION  
(Rule 1.53(b) Continuation-in-Part  
of Serial No. 09/638,872,  
Filed August 15, 2000)

: Attn: Application Branch

: Attorney Docket No. 2002-0069

THE COMMISSIONER IS AUTHORIZED  
TO CHARGE ANY DEFICIENCY IN THE  
FEE FOR THIS PAPER TO DEPOSIT  
ACCOUNT NO. 23-0975.

JC868 U.S. PTO  
10/05 3622  
01/24/02



**CLAIM OF PRIORITY UNDER 35 USC 119**

Assistant Commissioner for Patents,  
Washington, DC 20231

Sir:

Applicants in the above-entitled application hereby claim the date of priority under the International Convention of Japanese Patent Application No. 11-234688, filed August 20, 1999, as acknowledged in the Declaration of this application.

A certified copy of said Japanese Patent Application is of record in parent application

Serial No. 09/638,872, filed August 15, 2000.

Respectfully submitted,

Toshikazu TACHIKAWA et al.

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January 24, 2002

English translation of Official Letter  
in Taiwanese patent application

Notice of Office Action

Receiver: TOKYO OHKA KOGYO CO., LTD.

Mailed: June 19, 2003

1. Application No.: 089116541  
2. Title of the invention: NEGATIVE-WORKING PHOTORESIST  
COMPOSITION

3. Applicant: Name: TOKYO OHKA KOGYO CO., LTD.  
Address: Japan

4. Attorney:

5. Filing date: August 16, 2000

6. Priority data: 08/20/1999 Japan 11-234688

7. Examiner:

8. Content of decision:

Syllabus: The present invention is rejected.

Ground: Paragraph 2 of Article 20 of the Patent Law.

Reasons:

(1) The "negative-working photoresist composition" of  
the present invention is characterized in that the  
composition comprises an alkali-soluble resin, a  
radiation-sensitive acid-generating agent and a  
crosslinking agent.

(2) It is investigated that the crosslinking agent  
employed in the present invention is a commercial  
product, and those crosslinking agents from the  
same series are all conventionally known and used  
as disclosed in, for example, USP 5928837 and USP  
5700625. Accordingly, the claimed content of the  
present invention employs prior art or knowledge  
in a way people skilled in the same field may easily  
accomplish it. The present invention is thus hardly

considered as a creation of highly advanced technical thoughts, and is devoid of inventive steps.

In conclusion, the instant application fails to conform to the statutory patent requirements and therefore a patent should not be granted thereto in accordance with Paragraph 2 of Article 20 of the Patent Law.

# 經濟部智慧財產局專利核駁審定書

受文者：東京應化工業股份有限公司（代理人：  
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發文日期：中華民國九十二年六月十九日

發文字號：（九二）智專二（六）01061字

第092310607340號

一、申請案號數：0八九一一六五四一

二、發明名稱：負型光阻組成物

三、申請人：

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五、申請日期：八十九年八月十六日

六、優先權項目：

1 1999/08/20 日本11-234688

專利分類IPC(7)…G03F 7/038

受信日	發信日	本書
2003年6月19日	2003年6月19日	

七、審查人員姓名：劉瑞祥 委員

八、審定內容：

主文：本案應不予專利。

依據：專利法第二十條第二項。

理由：

(一) 本案所請「負型光阻組成物」特徵為組成物中含有碱可溶性樹脂、光酸生成劑及架橋劑。

(二) 經查本案所使用之架橋劑為市售商品，且同系列之架橋劑均為習知且習用者，如US 5928837、5700625所揭示，故本案所請為由習用技術、知識所顯而易知，且易於完成者，難謂高度技術思想之創作，不具進步性。

據上論結，本案不符法定專利要件，爰依專利法第二十條第二項，審定如主文。

局長 蔡練生

裝

訂

線

依照分層負責規定授權單位主管決行

如不服本審定，得於文到之次日起三十日內，備具再審查理由書一式二份及規費新台幣陸仟元整（專利說明書及圖式合計在五十頁以上者，每五十頁加收新台幣五百元，其不足五十頁者以五十頁計），向本局申請再審查。

